AMENDMENTS TO THE SPECIFICATION

Please amend the paragraph starting at page 5, line 21 as follows:

A first pellicle 32 is positioned between the projection system 24 and the first object table 18. The first pellicle 32 prevents or inhibits contamination from attaching and building up on a top surface 34 of the projection system 24. A second pellicle 36 is positioned between the projection system 24 and the substrate 28. The second pellicle 36 prevents or inhibits contamination from attaching to and building up on a bottom surface 38 of the projection system 24. By preventing and reducing the build up of contamination on one or more surfaces of the projection system 24, the pellicles 32 and 36 [[34]] reduce the adverse effects caused by scattering of the beam 14 during the projection process. Further, the ability to replace the pellicles 32 and 36 [[34]] independently increases the useful life of the projection system 24.

Please amend the paragraph beginning at page 7, line 17 as follows:

Now with reference to Figs. 2a and 2b, the first and second pellicles 32 and 36 [[34]] will be described. It should be understood by those have ordinary skill in the art that an embodiment described with relation to one pellicle may be used or modified to be used with the other pellicle. The first and second pellicles 32 and 36 [[34]] may be a hard pellicle or a soft pellicle as further described below. The first and second pellicles 32 and 36 [[34]] may have a width or diameter between about 250 mm and about 350 mm. A hard pellicle will have a thickness to prevent distortion, e.g., (bowing of the pellicle) due to gravity. A hard pellicle may have a thickness between about .5mm and about 1.5 mm. A hard pellicle may have a thickness between about .75 mm and about 1.25 mm. A hard pellicle may have a thickness between about 1.0 mm and 1.25 mm. A soft pellicle may have a thickness between about 10 microns and about 50 microns. A soft pellicle may have a thickness between about 20 microns and 40 microns. A soft

pellicle may have a thickness between about 25 microns and 35 microns. Those having ordinary skill in the art will understand that the ranges are exemplary and ranges between the maximum and minimum ranges disclosed are included, e.g. a hard pellicle may have a thickness between about .83 mm and about 1.17 mm.

Please amend the paragraph beginning at page 8, line 1 as follows:

The first and second pellicles 32 and 36 [[34]] in projection systems may be selected optical glass or synthetic fused silica for 365-nm, and synthetic fused silica for 248-nm, 193-nm and 157 nm. CaF_2 may be used for some elements at 193 nm, and as the primary material at 157 nm.

Please amend the paragraph beginning at page 10, line 24 as follows:

Next, the pellicle 32 is placed over the top surface 34 of the lens 24. The pellicle 32 may be placed on a moveable mounting means 40a, ~~(not shown),~~ a movable pellicle table, for example. The moveable mounting means 40a can be inserted into the lithographic projection apparatus 10 such that the pellicle 32 is positioned over the top surface 34 of the lens 24 in close proximity to the top surface 34. For example, the first pellicle 32 may be positioned, for example, within about 1 mm to about 8 mm, within about 3 mm to about 6 mm, within about 5 mm to about 8 mm or the like. The movable mounting means 40a is configured to allow the pellicle 32 to be easily removed and/or replaced when a surface of the pellicle 32 is contaminated to such an extent that the contamination adversly affects the image projected on the substrate 28. Additionally, the movable mounting means 40a allows the pellicle 32 to be moved out of the way of the top surface 34 of the lens 24 to allow the top surface 34 to be cleaned.

Please amend the paragraph beginning at page 11, line 4 as follows:

Next, a pellicle 36 is placed over a bottom surface 38 of the lens 24. The pellicle 36 may be placed or mounted on a second moveable mounting means 40b, ~~(now shown),~~ a second movable pellicle table, for example. The second moveable mounting means 40b will position the pellicle 36 in close proximity to the bottom surface 38 of the lens 24. That is, the moveable mounting means 40b can translate in the Y direction and the Z direction in order to position the second pellicle 36, e.g., within about 8 mm, within about 3 mm to about 6 mm, within about 5 mm to about 8 mm, or the like of the bottom surface 38 of the lens 24. Now the lithographic apparatus 10 is used as described above in the manufacturing of integrated circuits.

Please amend the paragraph starting at page 11, line 23 as follows:

If one or both pellicles 32 and 36 have contamination that adversely affects the image projected on the substrate 28, the pellicle or pellicles may be replaced. For example, the moveable mounting means 40a may be removed or partially removed from the lithographic projection apparatus 10 and the pellicle 32 with contamination thereon can be removed from the moveable mounting means 40a. A new pellicle 32 can be mounted onto the moveable mounting means 40a. The moveable mounting means 40a can then be reinserted into the lithographic projection apparatus 10 as described above.

Please amend the paragraph starting at page 11, line 30 as follows:

Alternatively, the second moveable mounting means 40b may be removed or partially removed from the lithographic projection apparatus 10 and the pellicle 36 with contamination thereon can be removed from the second movable mounting means 40b. A new pellicle 36 can be mounted onto the second mounting means 40b and the

second mounting means 40b can be reinserted into the lithographic projection apparatus 10 as described above.